

Supplementary Materials: Structural and Electric Properties of Epitaxial $\text{Na}_{0.5}\text{Bi}_{0.5}\text{TiO}_3$ -Based Thin Films

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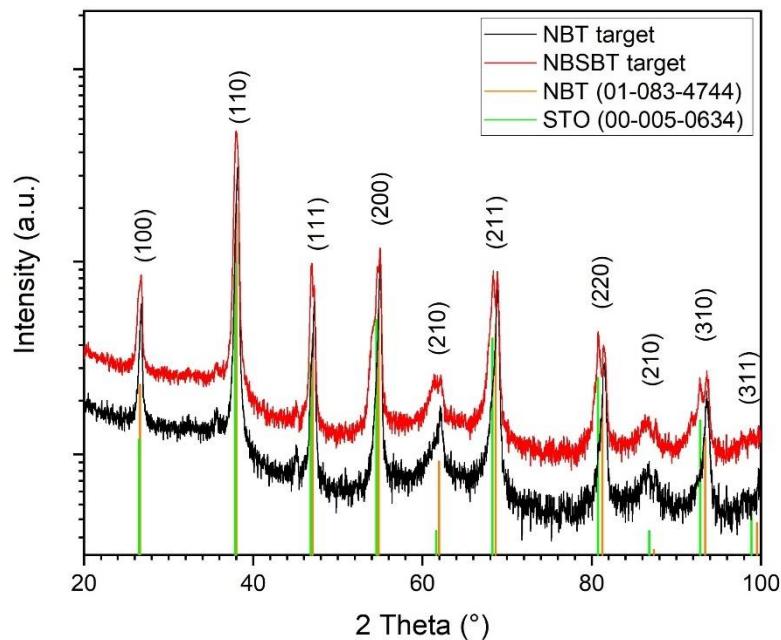


Figure S1. XRD scans showing the influence of the growth temperature on the growth of NBT films on LAO with a thickness of about 150 nm, the lines are taken from the ICDD PDF-4 database.

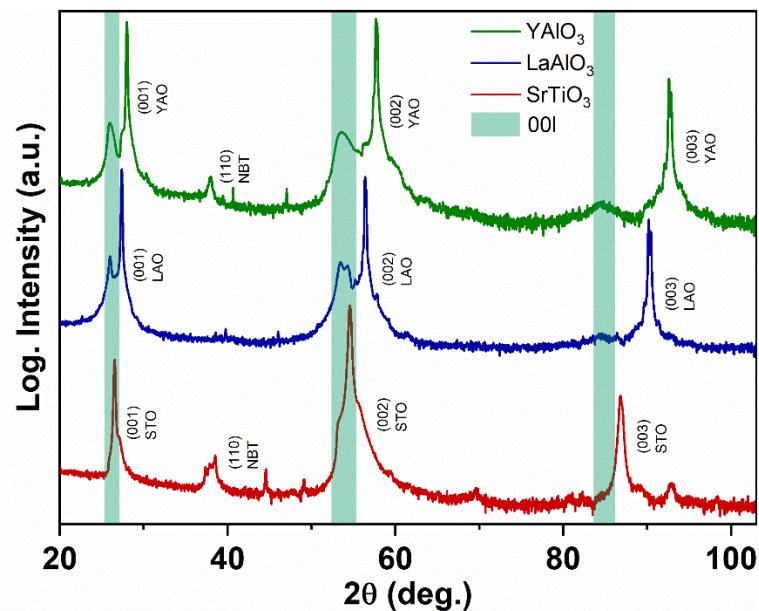


Figure S2. XRD scans showing the influence of the substrate on the growth of NBT films.